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**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

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No. PCT/IT2002/000774
FILING DATE: (new)
FIRST NAMED INVENTOR: .Maccalli et al.
GROUP ART UNIT:
ATTORNEY DOCKET NO.: 47966.14.1

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No. ¹	Document No. Number-Kind Code ²	Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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/SM/		WO02/38838	05/16/2002			<input type="checkbox"/>
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/SM/		GB 1 458 222	12/08/1976			<input type="checkbox"/>
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Examiner Initials	Cite No. ¹		T ⁷
/SM/		Zhang, J., et al., "Growth Characteristics of SiC in a Hot-Wall CVD Reactor with Rotation", Journal of Crystal Growth 241 (2002) pp. 431-438	<input type="checkbox"/>
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/Sylvia Macarthur/

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